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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q64410

Shinichi KANNA, et al.

RECEIVED

Appln. No.: 09/851,113

JAN 06 2003

Group Art Unit: 1752

Confirmation No.: 2319

TC 1700

Examiner: Rosemary E. Ashton

Filed: May 9, 2001

For: POSITIVE RADIATION-SENSITIVE COMPOSITION

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents
Washington, D.C. 20231

Sir:

This is responsive to the Office Action dated September 24, 2002. Please amend the above-identified application as follows.

IN THE CLAIMS:

Please cancel Claim 9 without prejudice or disclaimer.

Please enter the following amended claims:

1. (Amended) A positive radiation-sensitive composition comprising:
- (a) a resin whose solubility in an alkali developer increases by the action of an acid;
 - (b) a compound that generates a carboxylic acid having a molecular weight of 100 or less upon irradiation with an actinic ray or a radiant ray;
 - (c) a surfactant; and
 - (d) a solvent,

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